

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3091	photo near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S2	24887	photoresist near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S3	27744	S1 or S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S6	15166	i-line or KrF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S7	1807	S3 and S4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S8	10744	ArF or UvU or EUF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S9	128	S7 and S8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S10	411399	resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S11	66	S9 and S10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:51
S12	2	"4491628".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56

S13	1	10/719083	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56
S14	336	("4491628").URPN.	USPAT	OR	ON	2005/08/25 08:43
S15	965	tri-level	USPAT	OR	ON	2005/08/25 08:43
S16	68113	photoresist	USPAT	OR	ON	2005/08/25 08:43
S17	21	S15 near S16	USPAT	OR	ON	2005/08/25 10:05
S18	454581	polymer	USPAT	OR	ON	2005/08/25 10:05
S19	365962	silicon	USPAT	OR	ON	2005/08/25 10:06
S20	191357	mask	USPAT	OR	ON	2005/08/25 10:06
S21	1	S18 near S19 near S20	USPAT	OR	ON	2005/08/25 10:09
S22	1	silicon near polymer near mask	USPAT	OR	ON	2005/08/25 10:09
S23	1	silicon near polymer near etch	USPAT	OR	ON	2005/08/25 10:09
S24	357	S18 near S20	USPAT	OR	ON	2005/08/25 10:14
S25	3334	i-line	USPAT	OR	ON	2005/08/25 10:14
S26	191357	mask	USPAT	OR	ON	2005/08/25 10:14
S27	2761	S25 and S26	USPAT	OR	ON	2005/08/25 10:15
S28	365962	silicon	USPAT	OR	ON	2005/08/25 10:15
S29	2131	S27 and S28	USPAT	OR	ON	2005/08/25 10:15
S30	186985	poly	USPAT	OR	ON	2005/08/25 10:15
S31	692	S29 and S30	USPAT	OR	ON	2005/08/25 10:53
S32	1874	gas near absorbing	USPAT	OR	ON	2005/08/25 10:54
S33	766	oxygen near absorbing	USPAT	OR	ON	2005/08/25 10:54
S34	200051	resist	USPAT	OR	ON	2005/08/25 10:54
S35	96988	spin	USPAT	OR	ON	2005/08/25 10:54
S36	14776	bake	USPAT	OR	ON	2005/08/25 10:54
S39	151804	water adj soluble	USPAT	OR	ON	2005/08/25 10:56
S40	454581	polymer	USPAT	OR	ON	2005/08/25 10:56
S41	20443	S39 near S40	USPAT	OR	ON	2005/08/25 10:56
S42	3403	S35 and S36	USPAT	OR	ON	2005/08/25 10:56
S43	36	S41 and S42	USPAT	OR	ON	2005/08/25 10:57
S44	30	S43 and S34	USPAT	OR	ON	2005/08/25 11:04
S46	2594	S32 or S33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:57
S50	195	S34 and S46	USPAT	OR	ON	2005/08/25 11:05
S51	23	S50 and S39	USPAT	OR	ON	2005/08/25 11:14

S52	53	organic adj polysilane	USPAT	OR	ON	2005/08/25 11:14
S53	68113	photoresist	USPAT	OR	ON	2005/08/25 11:14
S54	8	S52 and S53	USPAT	OR	ON	2005/08/25 14:15
S55	0	organic adj polysilane adj photoresist	USPAT	OR	ON	2005/08/25 13:46
S56	0	organic adj polysilane adj resist	USPAT	OR	ON	2005/08/25 13:46
S57	0	organic adj polysilane near resist	USPAT	OR	ON	2005/08/25 13:46
S58	13	organic adj polysilane and resist	USPAT	OR	ON	2005/08/25 13:46
S61	1	10/712,446	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 14:16